

Title (en)

Use of a Resist Composition for Immersion Exposure and Pattern Formation Method Using the Composition

Title (de)

Benutzung einer Resistzusammensetzung für die Immersionslithographie und Verfahren zur Herstellung von Mustern unter Verwendung dieser Zusammensetzung

Title (fr)

Utilisation d'une composition de réserve pour la lithographie par immersion et procédé de formation de motifs à l'aide de ladite composition

Publication

EP 1566693 A2 20050824 (EN)

Application

EP 05002940 A 20050211

Priority

JP 2004044795 A 20040220

Abstract (en)

A resist composition for immersion, comprises: (A) a resin of which solubility in an alkali developer increases under an action of an acid; (B) a photoacid generator; and (C) a mixed solvent containing an alkylene glycol alkyl ether carboxylate and a propylene glycol monomethyl ether.

IPC 1-7

G03F 7/004; **G03F 7/039**; **G03F 7/20**

IPC 8 full level

G03F 7/004 (2006.01); **G03F 7/039** (2006.01); **G03F 7/20** (2006.01); **H01L 21/027** (2006.01)

CPC (source: EP KR US)

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Cited by

EP1795961A1; EP1795963A1; EP1795960A3; US7368220B2; US8697329B2; US7790351B2; US7504194B2; US8679724B2; US9081279B2; US9709891B2; EP1767992A1

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EP 1566693 A2 20050824; **EP 1566693 A3 20061213**; **EP 1566693 B1 20180523**; JP 2005234330 A 20050902; JP 4365236 B2 20091118; KR 101110150 B1 20120208; KR 20060042109 A 20060512; TW 200532378 A 20051001; TW I354186 B 20111211; US 2005186503 A1 20050825; US 7326516 B2 20080205

DOCDB simple family (application)

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